

INNER TRACKER SUMMARY

◦ SIMULATION:

- ~ RADIATION ENVIRONMENT
- ~ DIGITIZATION / TRACKING

◦ 3GEN OPTION:

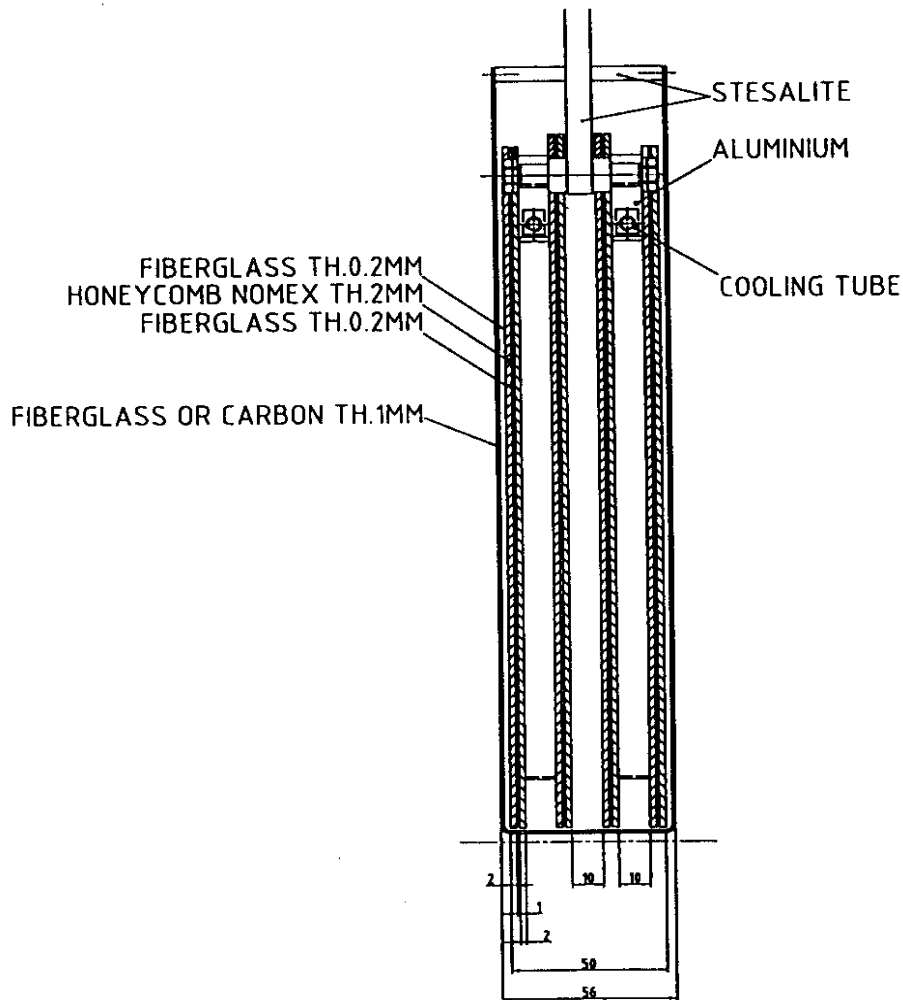
- ~ INVESTIGATION OF SPARKING BEHAVIOUR
- ~ DETECTOR OPTIMIZATION

◦ SILICON OPTION:

- ~ STATION LAYOUT
- ~ DETECTOR SPECIFICATIONS
- ~ MANUFACTURERS

V. Taranov

→ LHCb Note 2000-013



INNER TRACKER SILICON STATION

DETECTOR MODEL:

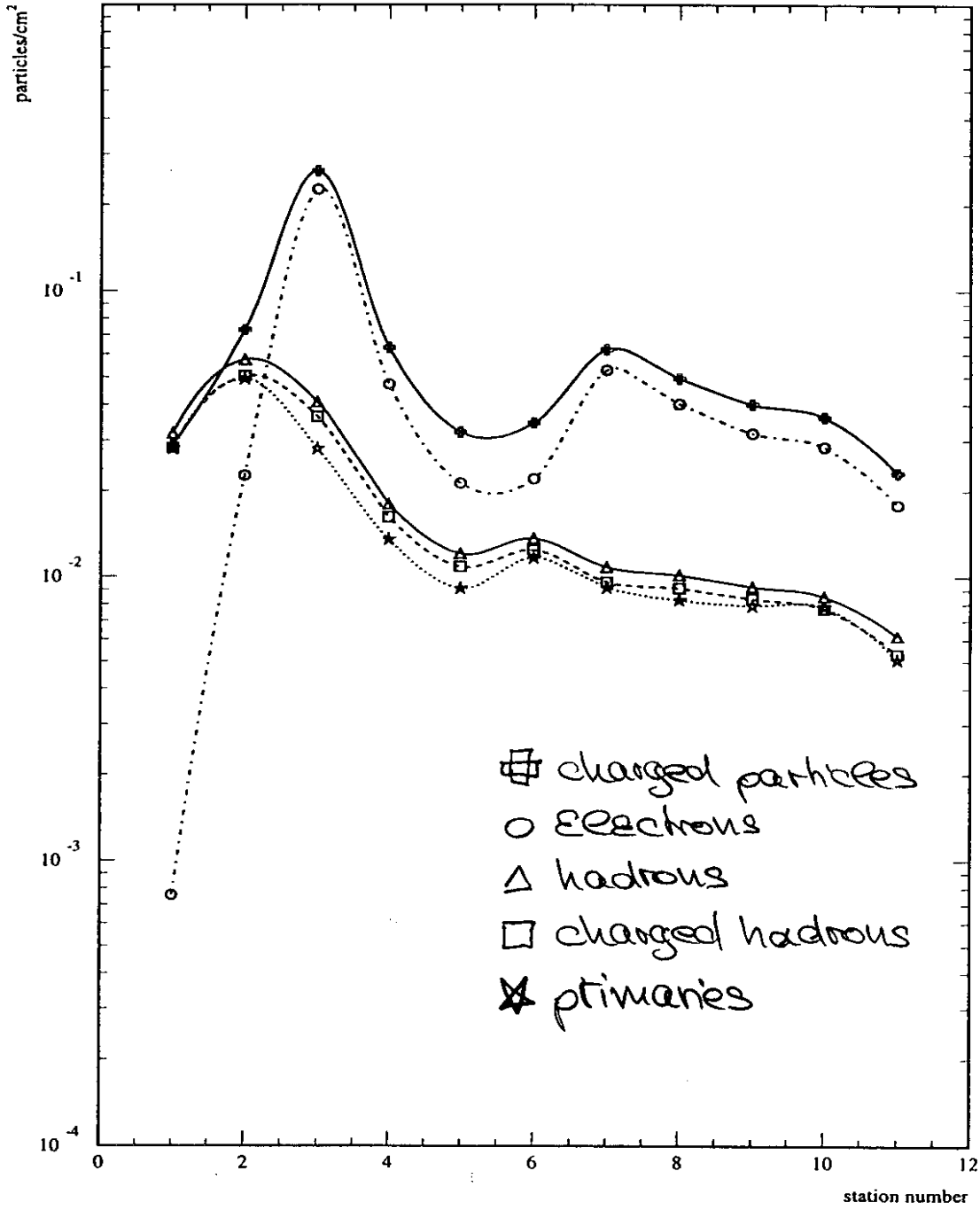
- 4 LAYER SILICON, 300 μ m
- SUPPORTS
- FRAMES
- COOLING PIPES

SUMMARY

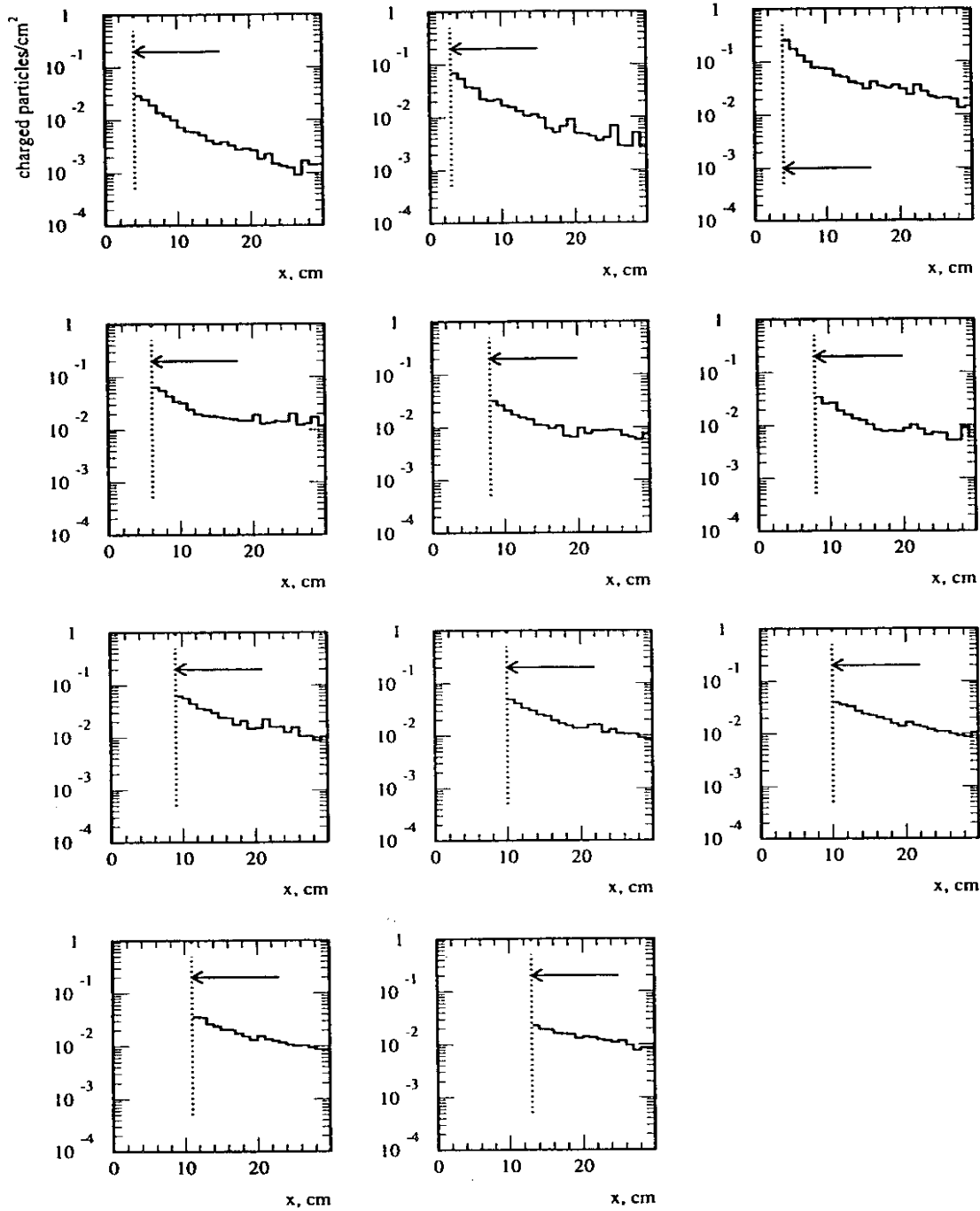
Value of	per 1 int.	at 16 MHz
charged hadrons (\simeq primary charged)	5×10^{-2}	8×10^5 /cm ² /s
charged particles (charged hadrons + e)	3×10^{-1}	4.8×10^6 /cm ² /s
cumulatives		
charged hadrons	≈ 10	1.6×10^8 /station/s
charged hadrons + e	≈ 100	1.6×10^9 /station/s
dose level (per year)		
station 03	$\approx 10^{-8}$	1.6 Mrad /year
station 07	2×10^{-9}	320 krad /year
chip location	$\approx 10^{-9}$	160 krad /year

1 MeV-equivalent neutrons: $\sim 5 \times 10^{13}$ /cm²/10y

Inner tracker silicon layers maximal particles flux



Inner tracker silicon layers charged particles flux



CONCLUSION :

- With the data provided by Vadim Talanov, we estimated the probability to have 2 or more particles in a strip (200 μm x 20cm) :
 - in the case of the maximum flux (tracker 03)
 - taking into account the probability to have several interactions in a bunch.

→

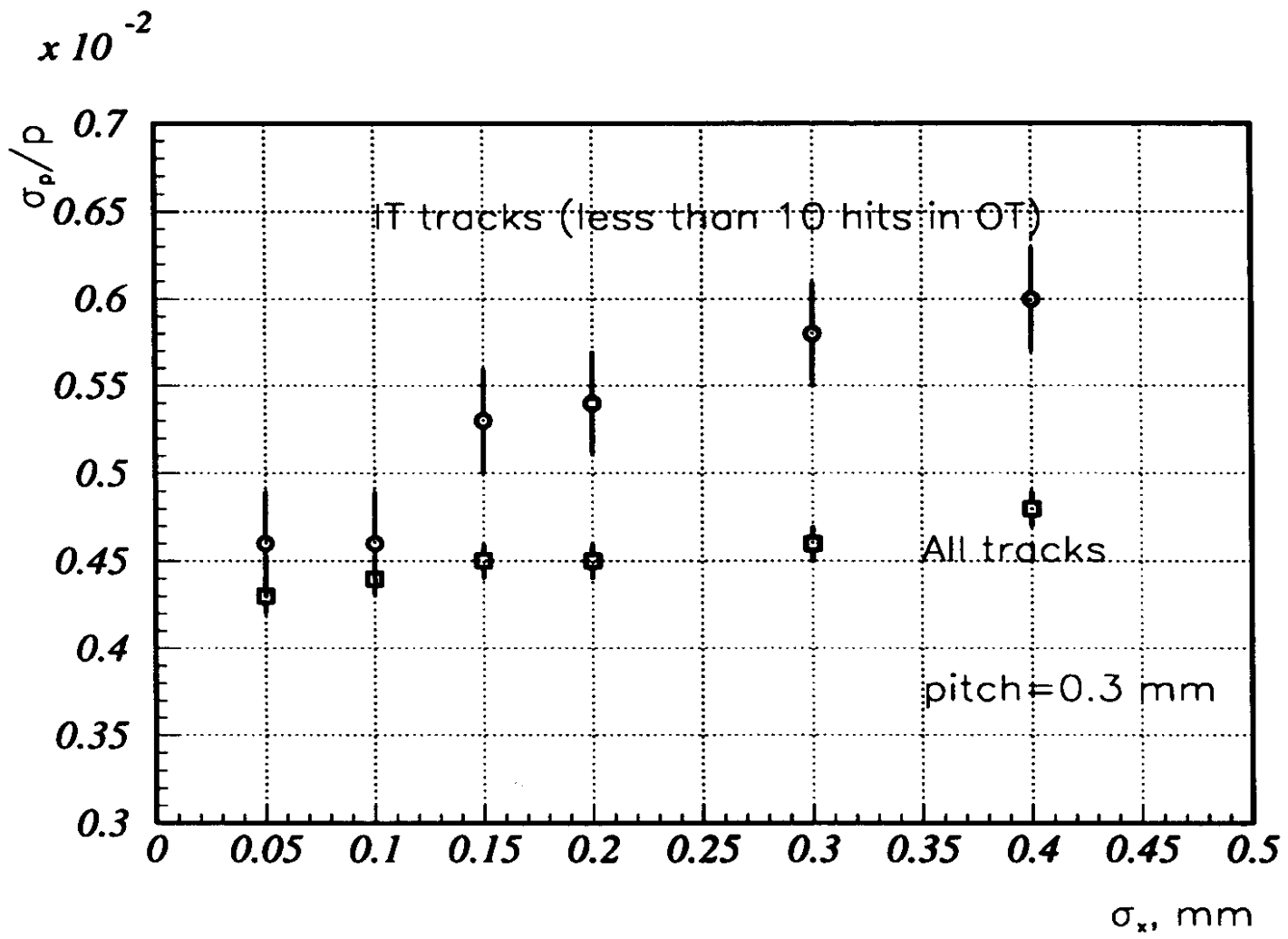
$$P_{\text{Cor}}(N \geq 2) = 1.28 \cdot 10^{-3} \quad \text{acceptable}$$

- We have tried to define a geometry

But we still have to think about

- the transition to the outer tracker (T2, T10, T11)
- where to put the electronic
- test the cooling system and change it if needed, ...
- ...

SPATIAL RESOLUTION



A. Polouektov / F. RONGA
using "Tracking Test"

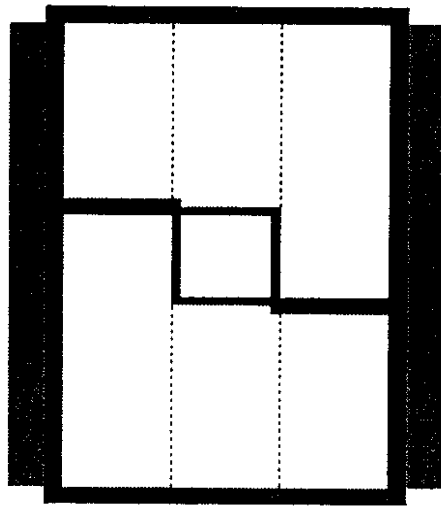
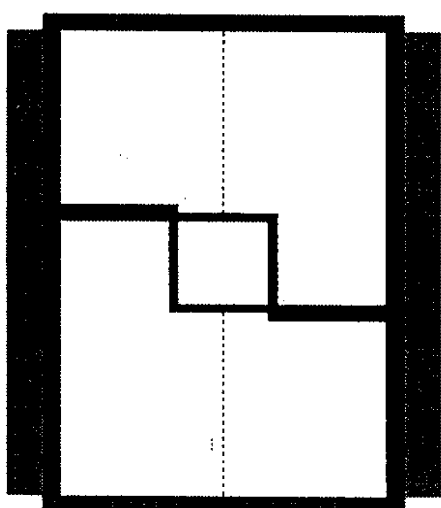
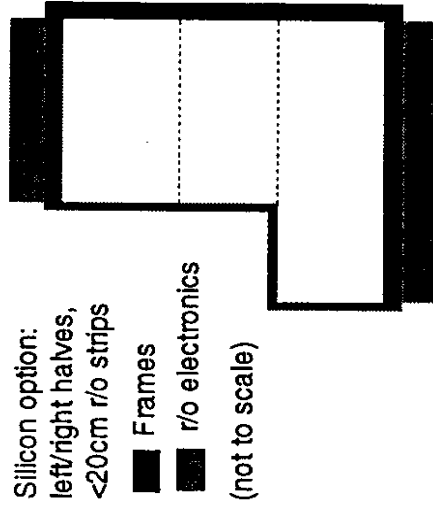
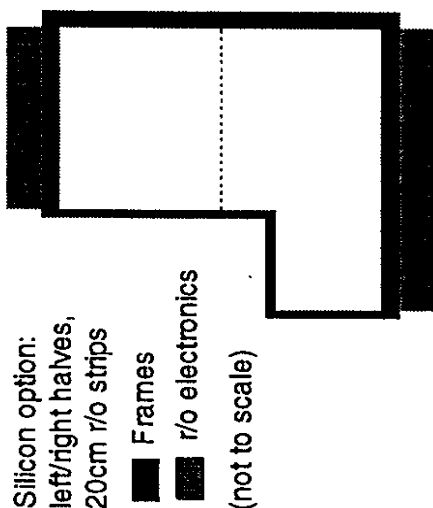
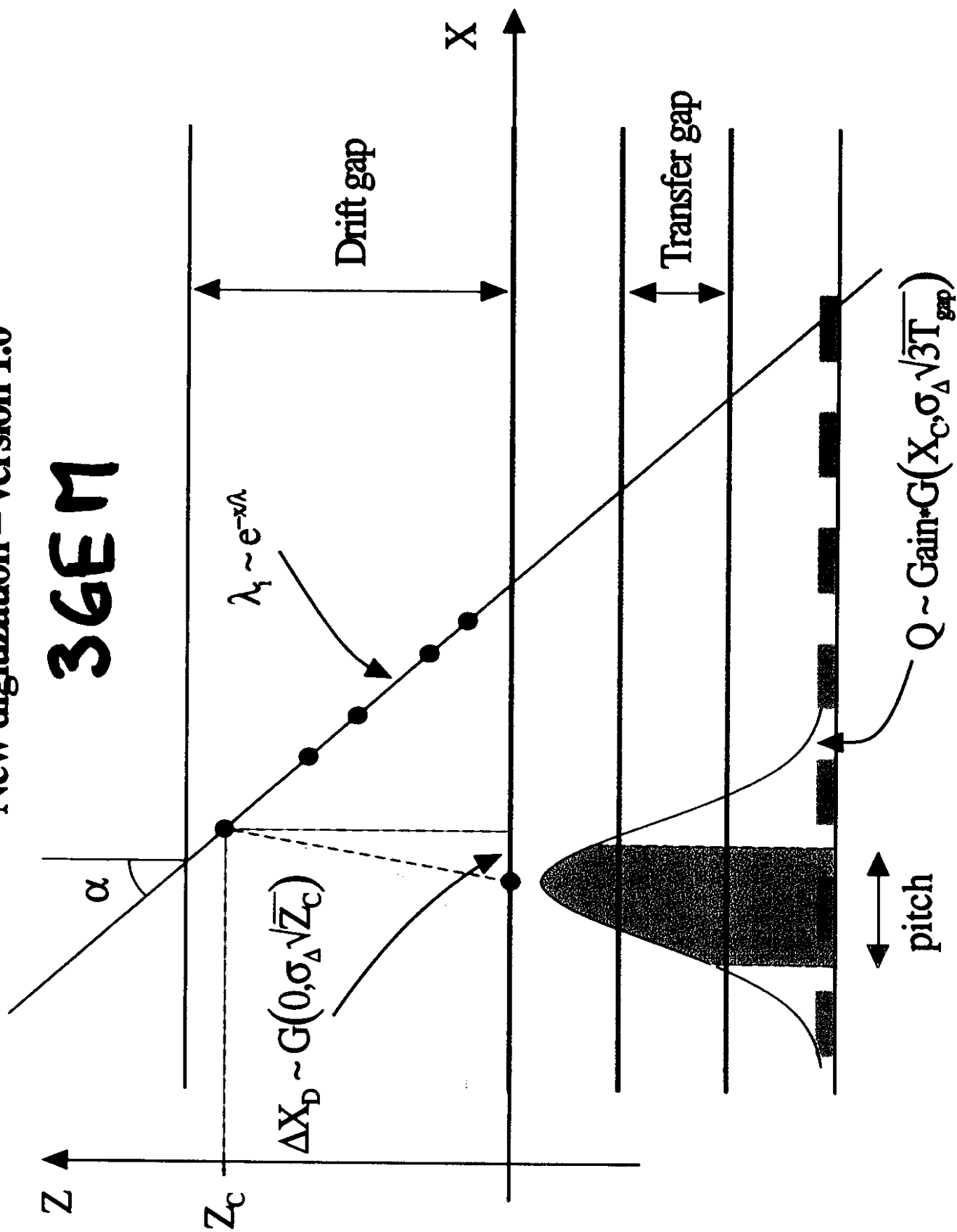


Figure 4: Possible layout of Silicon detector with left/right half-stations sketch on left assumes two vertical r/o sectors (the preferred solution), sketch on right with three vertical r/o sectors (necessary if r/o strips cannot be made long enough due to S/N limitation)

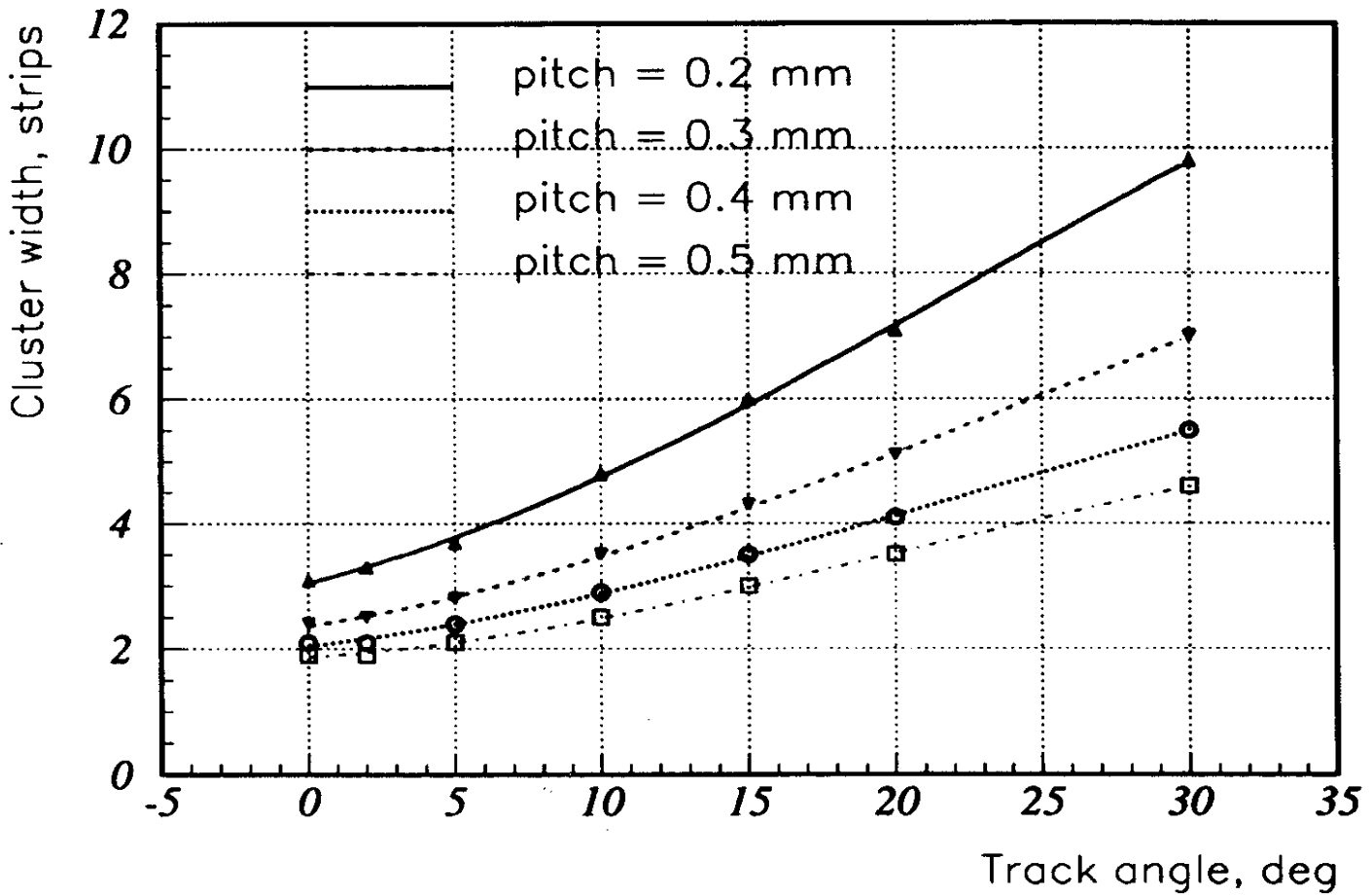
PREFERRED

⇒ FRAMES OUT OF MAX. FLUX
 ⇒ FIXATION TO OTR HALF-STATIONS
 ⇒ 3 GEN OPTION

3GEM



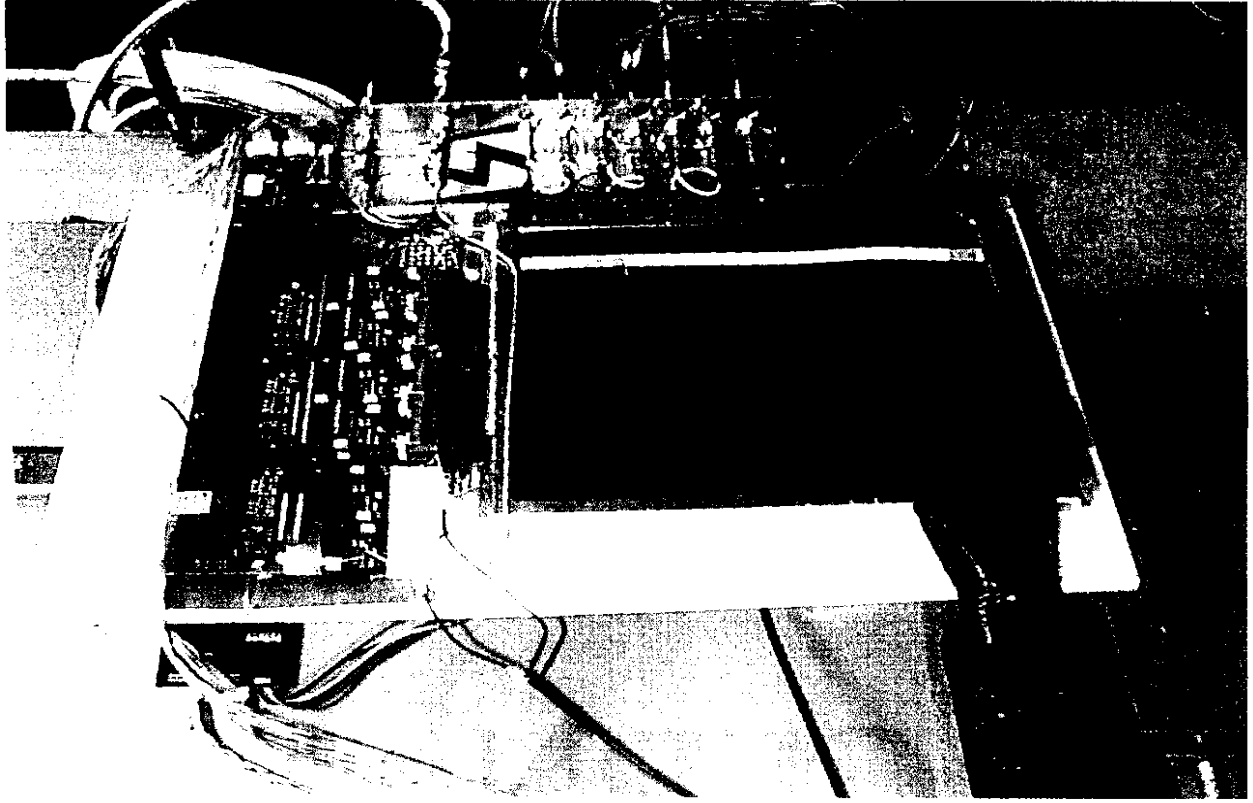
CLUSTER WIDTH



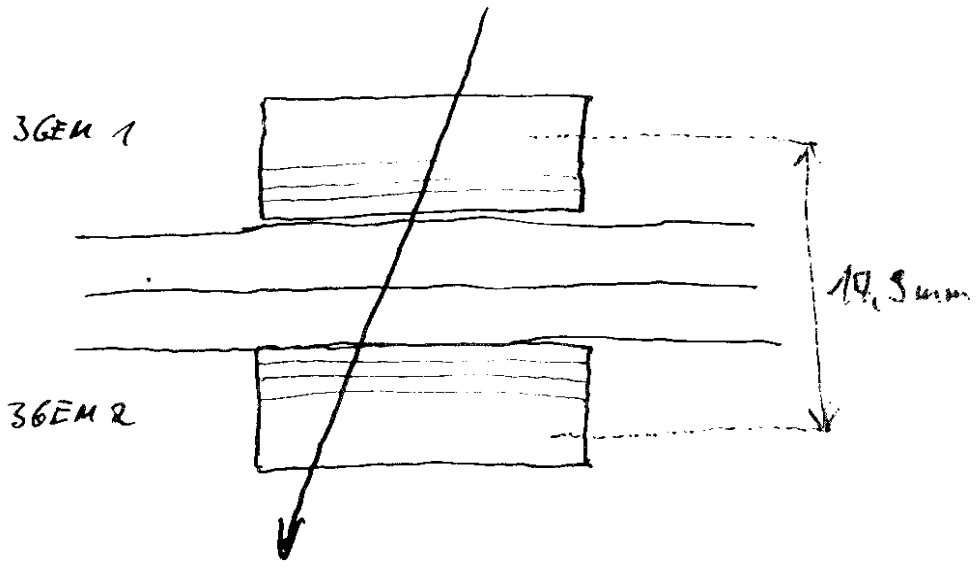
Need interaction with hardware IT group to tune settings

SEM

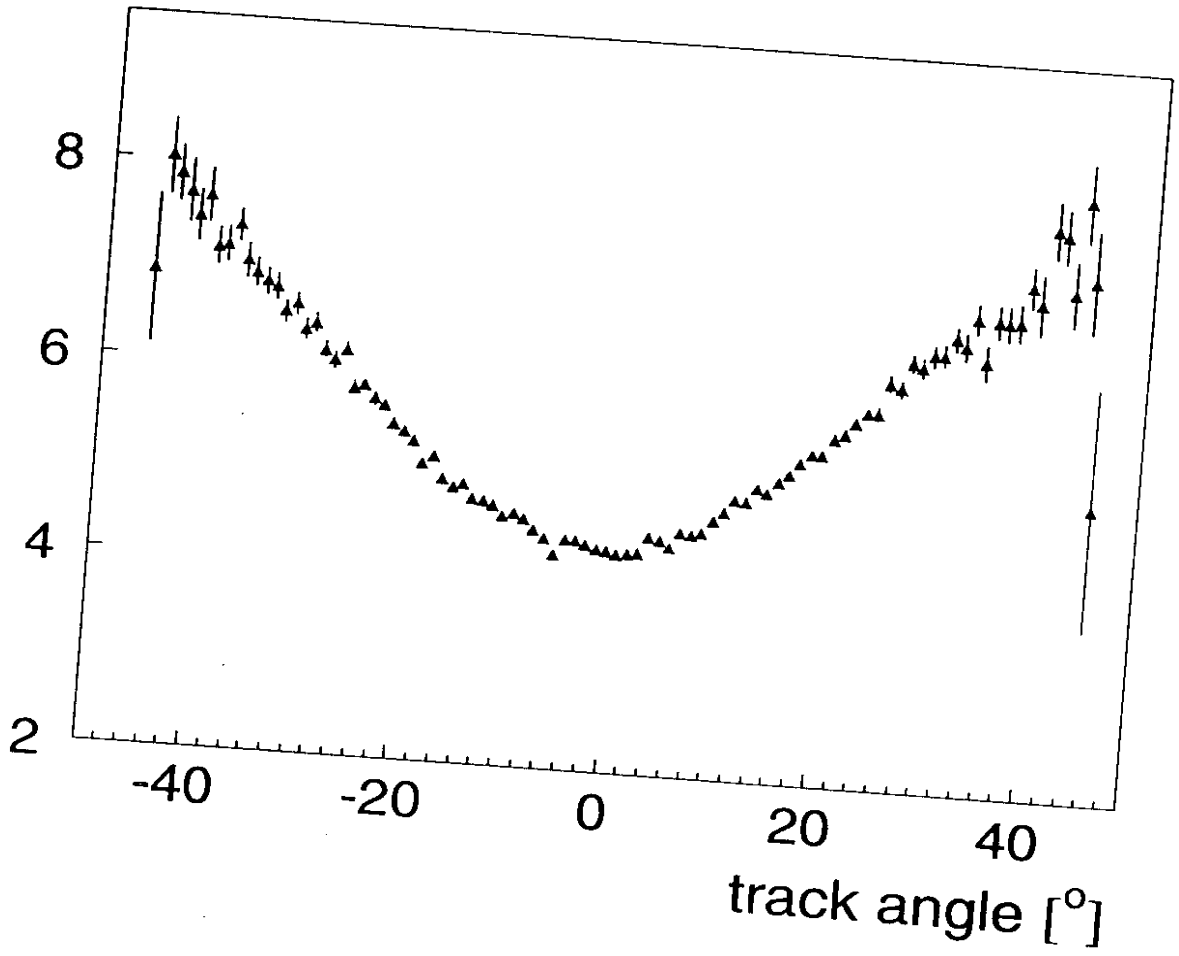
Cosmics setup

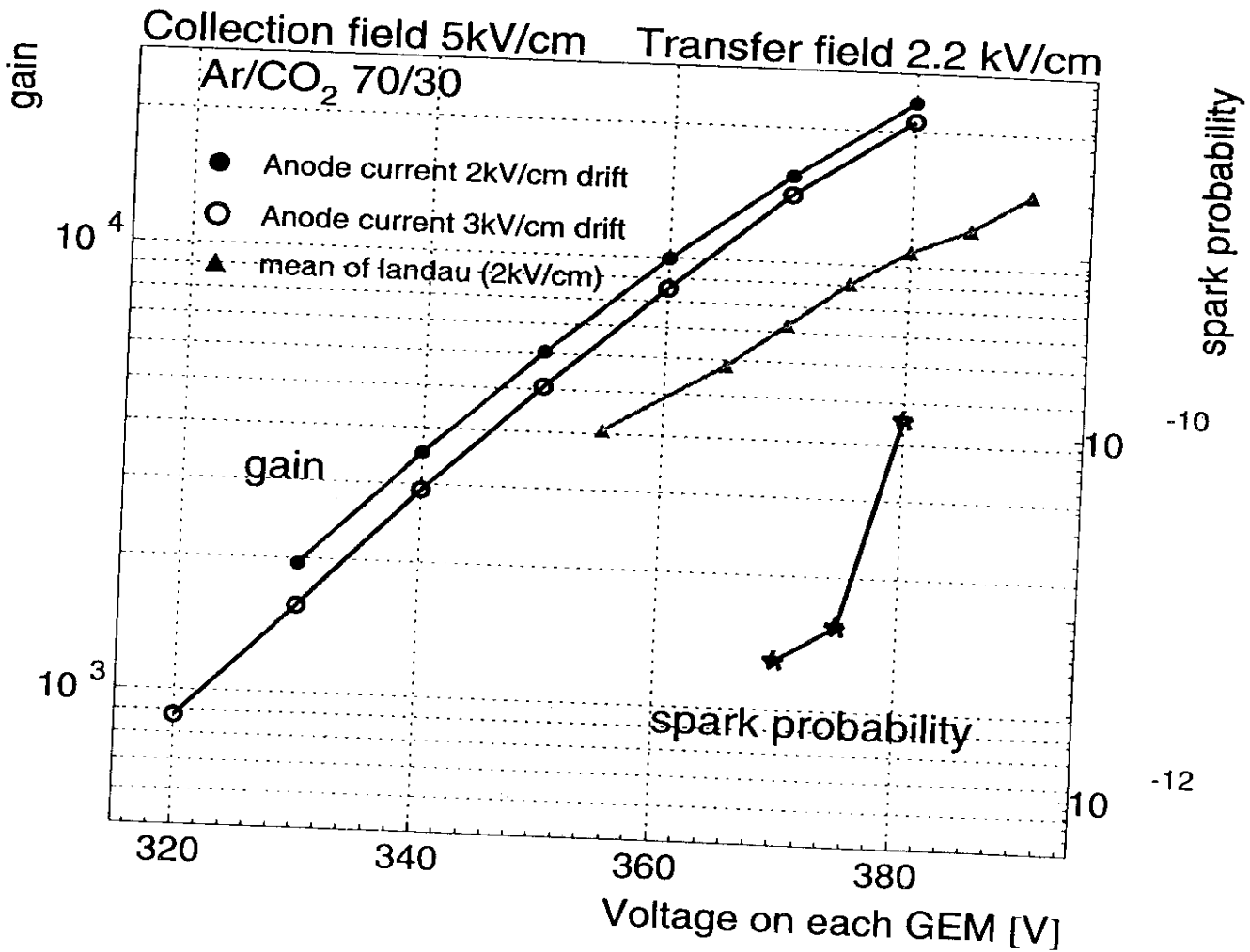


two 10cm x 10cm scintillators



channels over threshold





PSI test / "Zürich" 3GEM

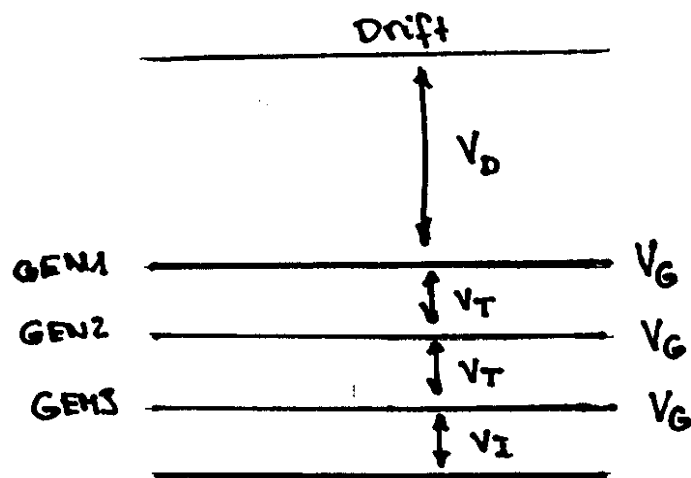
SPARK PROBABILITY 1 ORDER OF
 MAGNITUDE SMALLER THAN
 PRESENTED IN FEBRUARY!

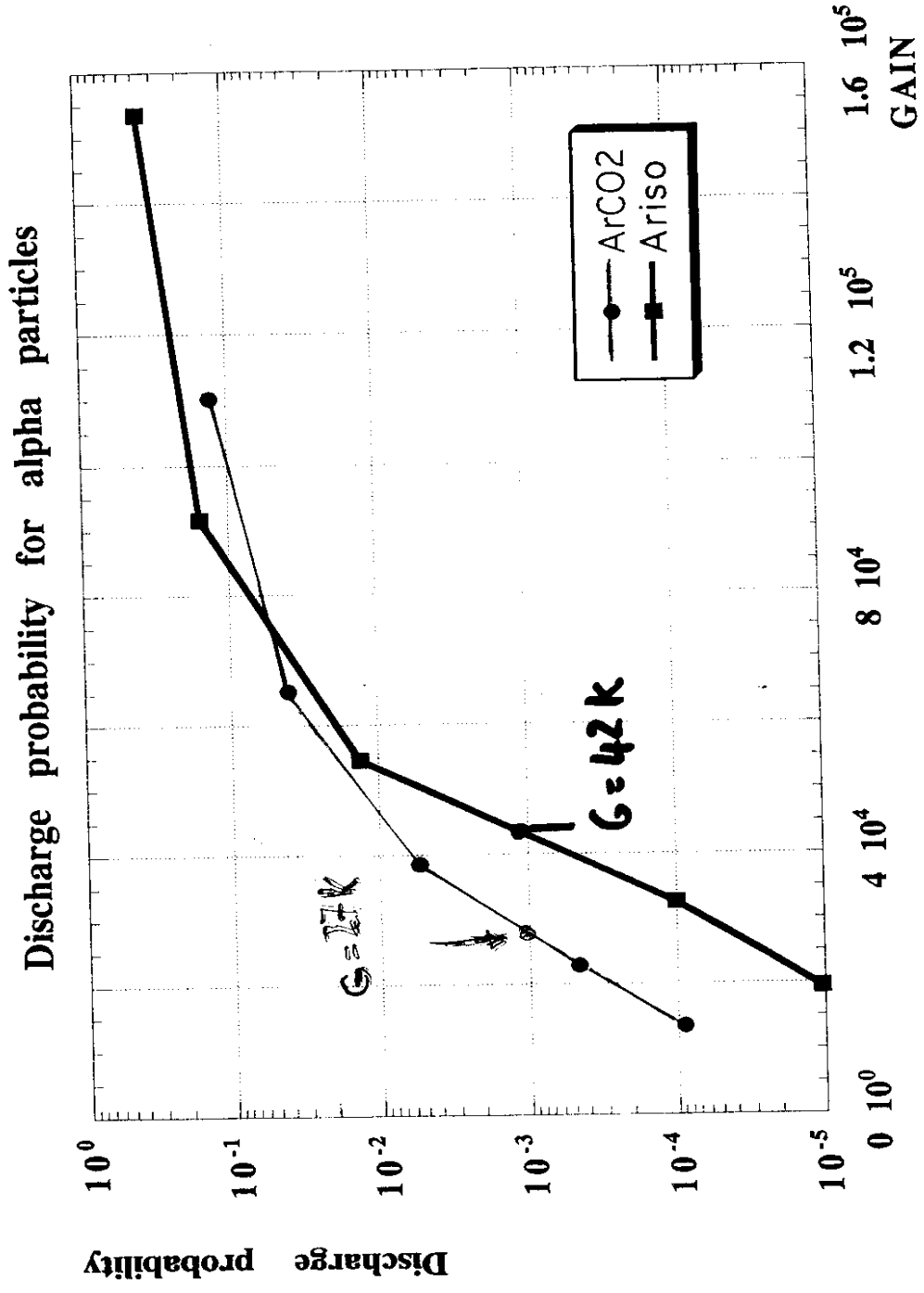
Study of discharges in triple GEM prototype

J.P.Perroud, IPHE, Lausanne

24, may, 2000

- Standard GEM pitch $140\ \mu\text{m}$, holes $70\ \mu\text{m}$, $5\ \mu\text{m}$ Cu
- Size $30 \times 30\ \text{mm}^2$
- Spacing drift $3\ \text{mm}$, transfer $1\ \text{mm}$, induction $1\ \text{mm}$
- Readout anode of $8\ \text{mm}$ in diameter
- Discharges triggered by alpha particles
- Two gas mixtures tested argon-isobutane and argon- CO_2





Argon-isobutane (90,10)

- $V_g = 315 \text{ V}$
- average discharge size 6.7 nC or 4.2×10^{10} electrons

Number of discharges	Defect
25042	GEM3
422400	GEM2
11067	GEM3
136200	GEM3
57630	GEM2
500	GEM3
257000	GEM3
Total 909800	
Average 130000	

Argon-CO2 (70,30)

- $V_g = 415 \text{ V}$
- average discharge size 9.4 nC or 5.9×10^{10} electrons

Number of discharges	Defect
100	GEM3
19810	GEM1
2160	GEM3
481	GEM3
15227	GEM1
22870	GEM2
41790	GEM2
Total 102400	
Average 14600	

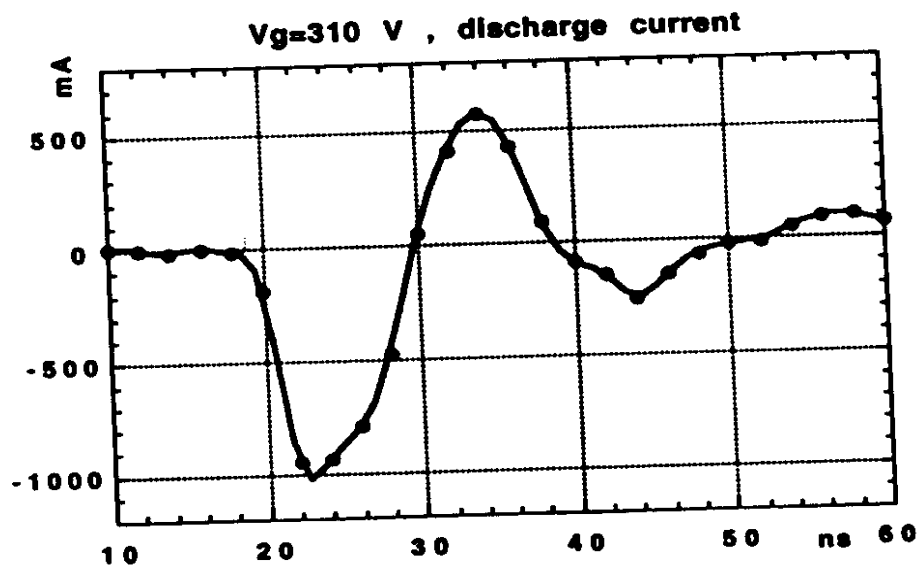
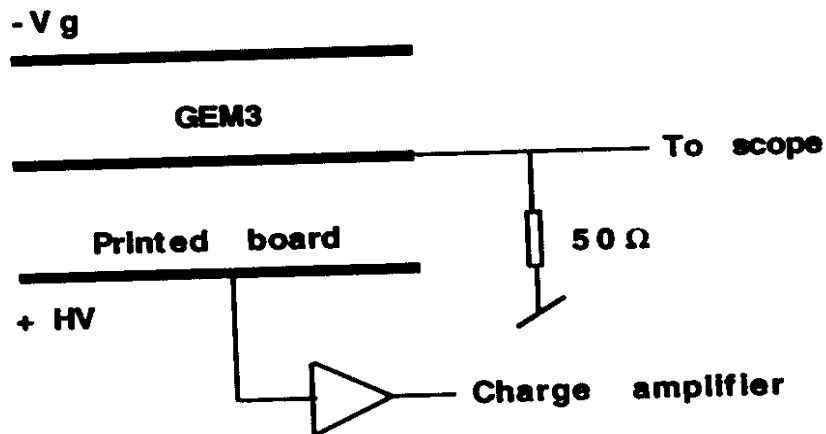
Hot spot: 8×10^5 electrons/cm²/s
Spark probability: $\approx 10^{-11}$ /electron
 $\Rightarrow \approx 100$ sparks/cm²/year

Measurement of discharge current

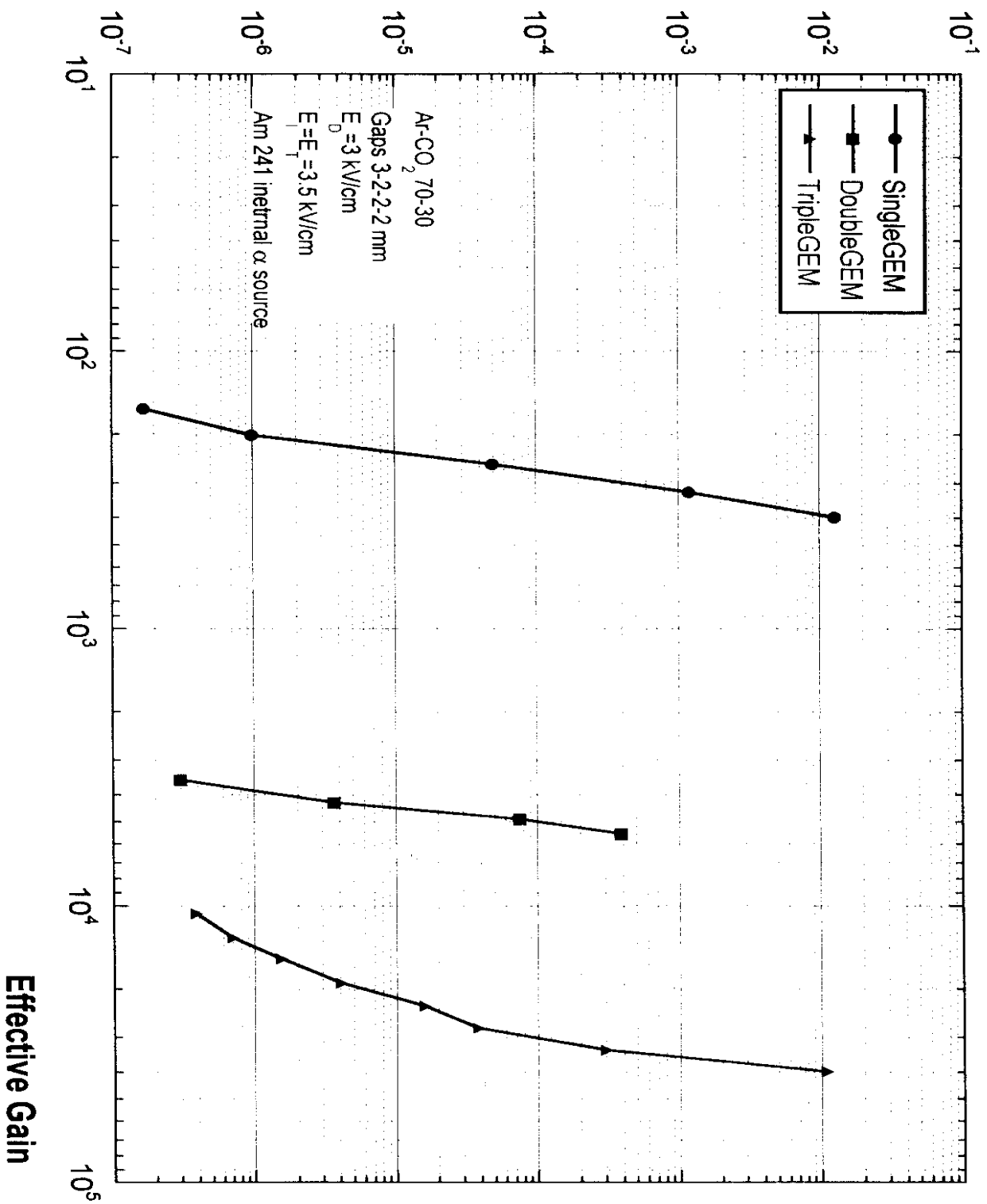
GEM capacity 450 pF

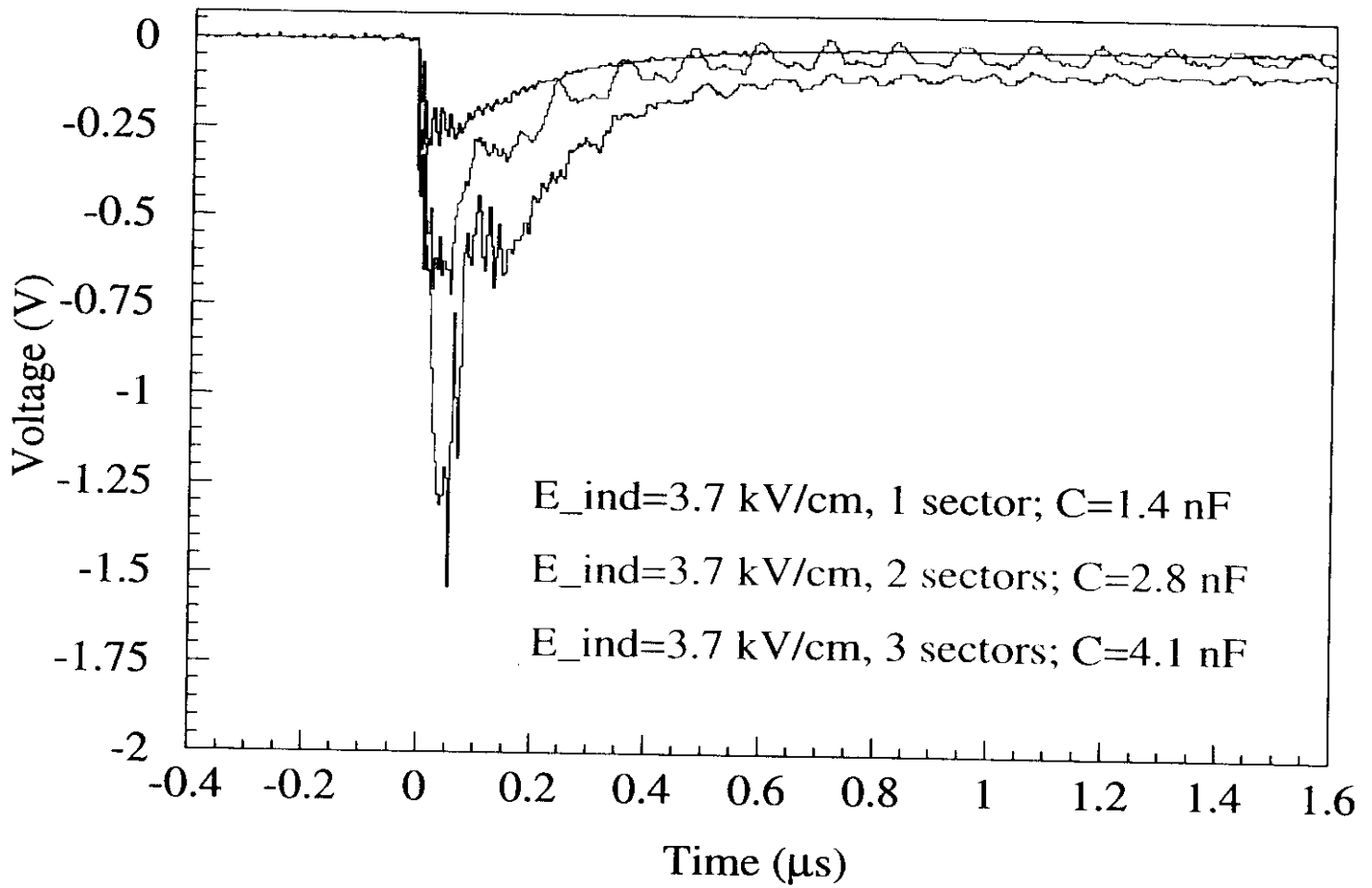
	Ar-CO2	Ar-Isobutane
Discharge size:	9.4 nC	6.7 nC
GEM voltage	415 V	315 V
Equivalent capacity	22.6 pF	21.3 pF

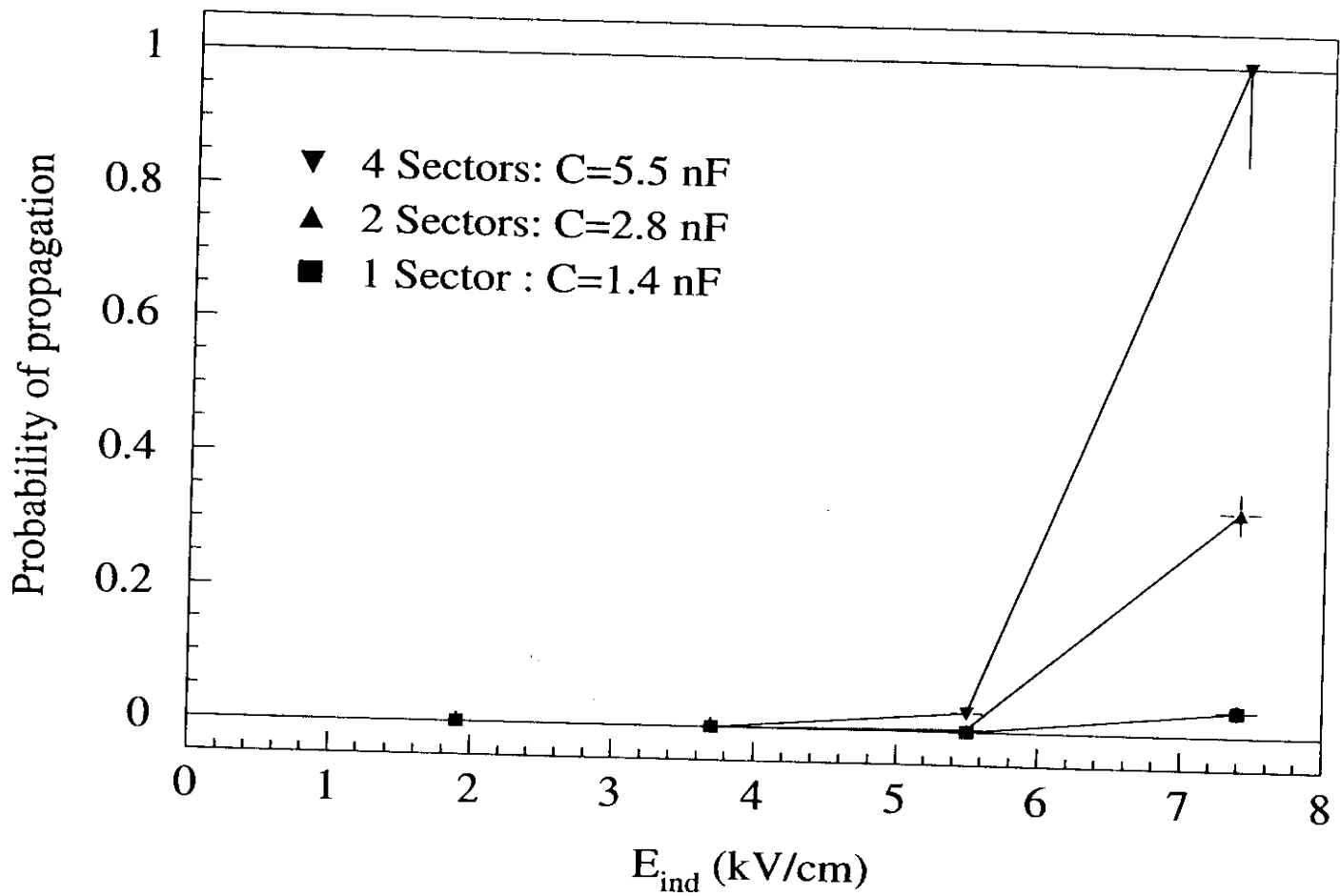
seems not to depend on the GEM capacity
 Only a small fraction of the GEM capacity is discharged



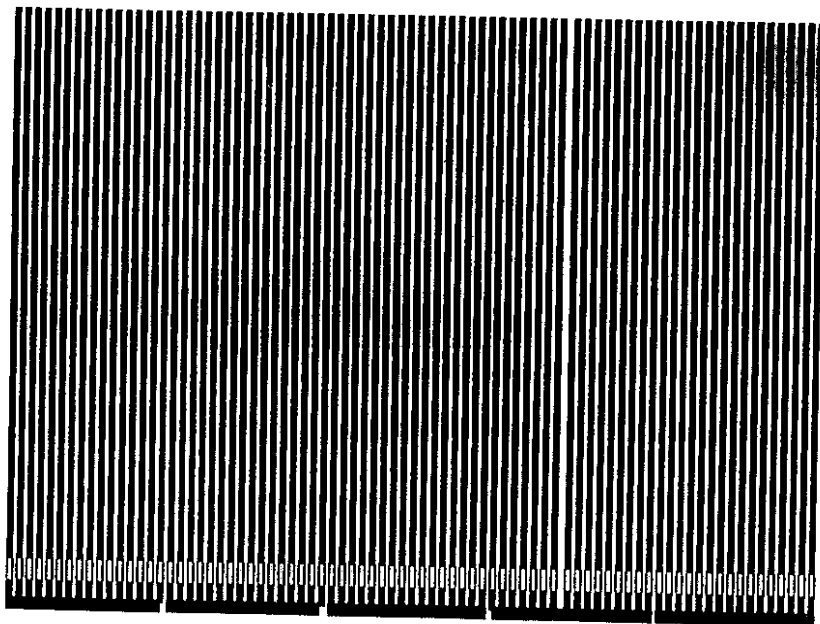
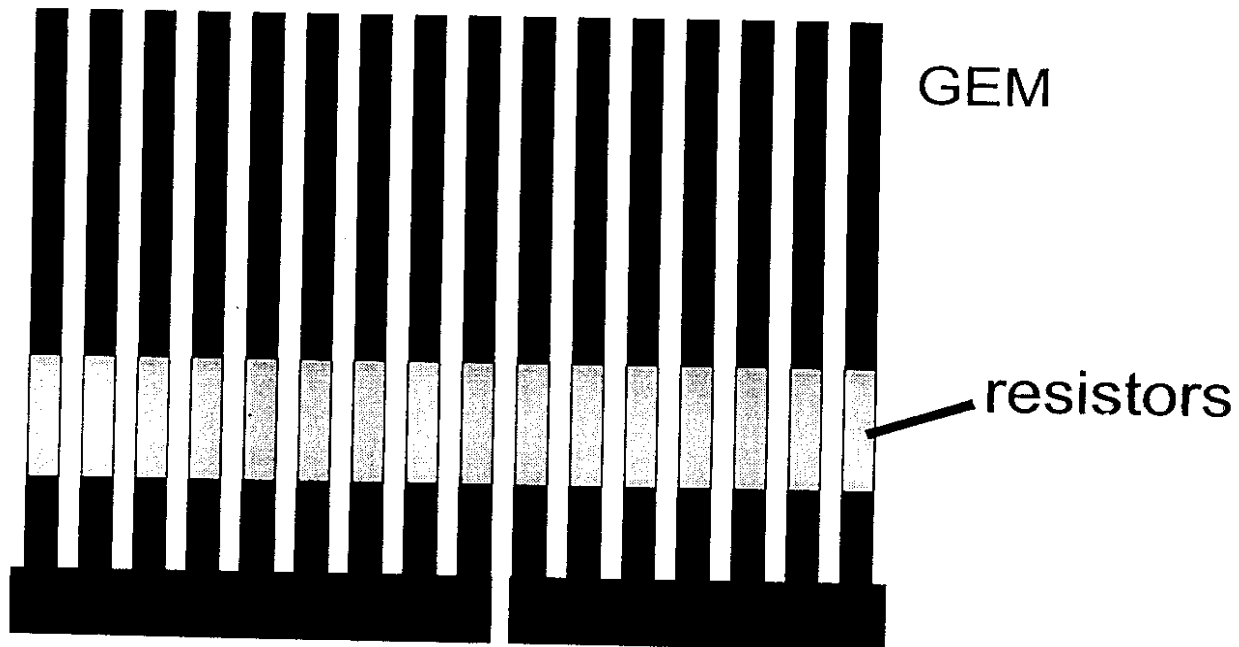
Discharge Probability / α particle





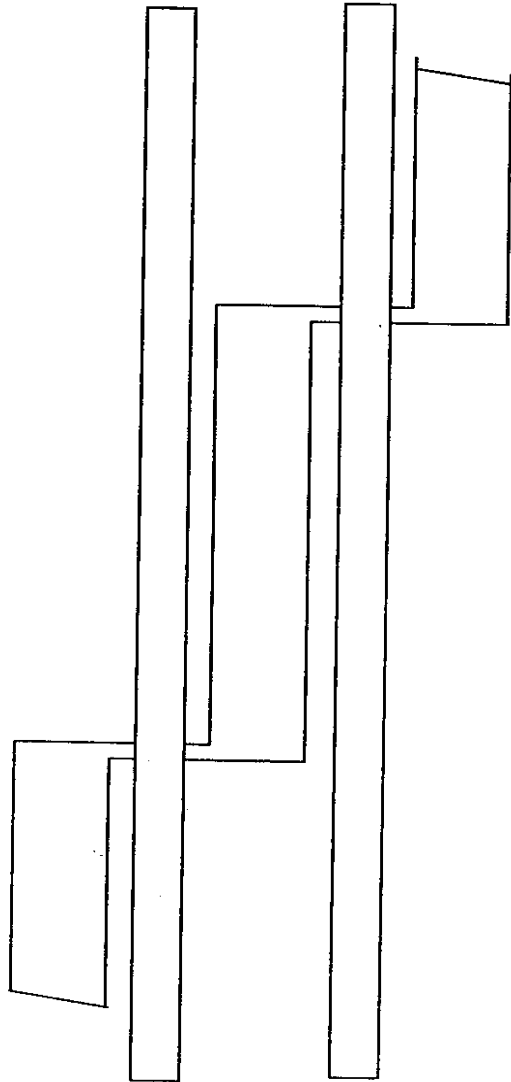


1mm segmentation



L. Chekhman

PCB design

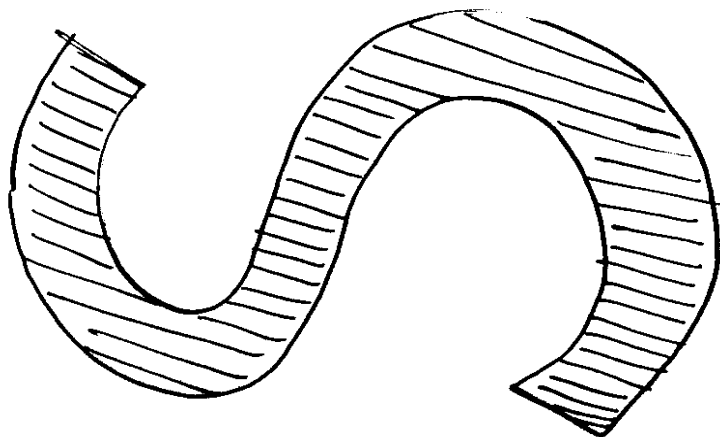
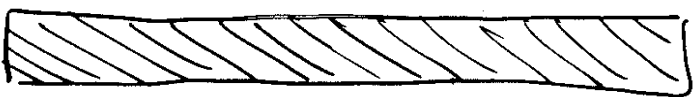
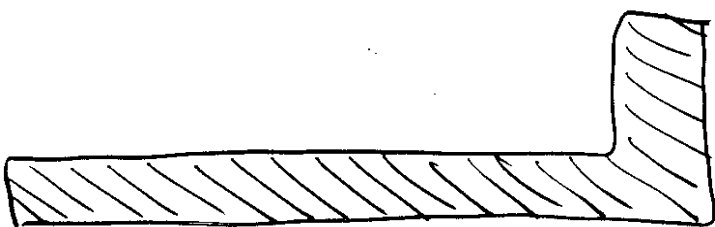
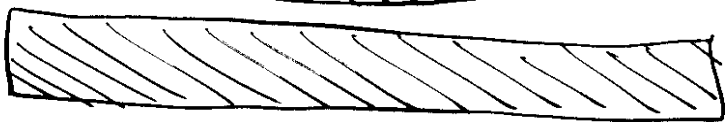
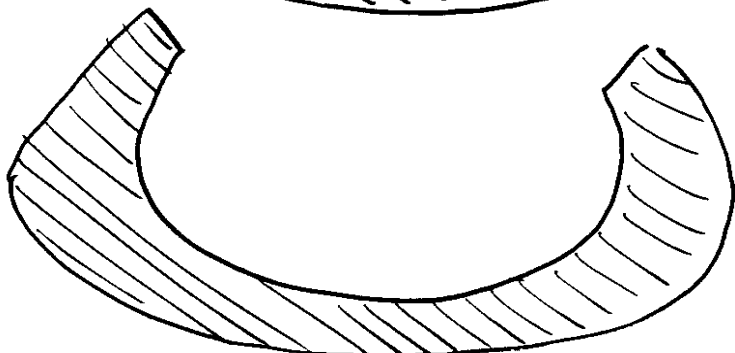
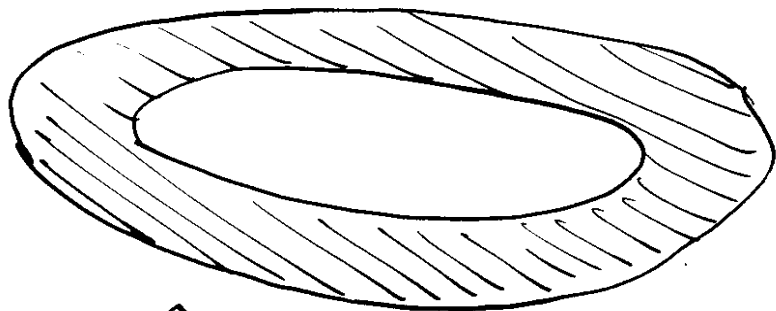
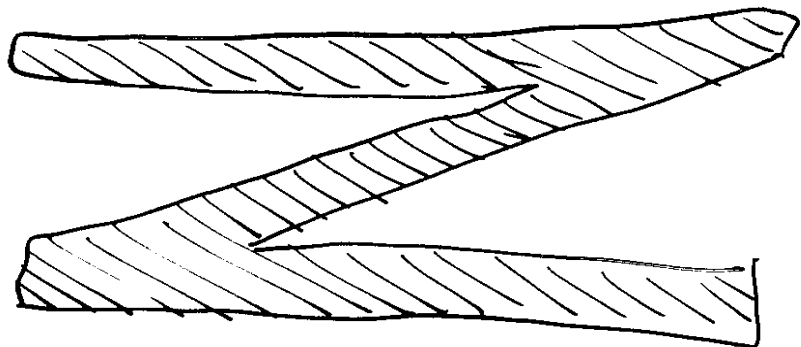


150um - bottom strip
60 um - top strip

50um kapton
400um pitch
4mm - zigzag pitch

capacitance (pF/cm):

	Meas.	Calc.
Top	0.54	0.32
bottom	0.73	0.62



Status report on the Beetle development

Testchips (2mm x 2mm)

- BeetleMA (frontend for multianode-readout)
- BeetleCO (comparator)
- BeetlePA (pipeline amplifier)

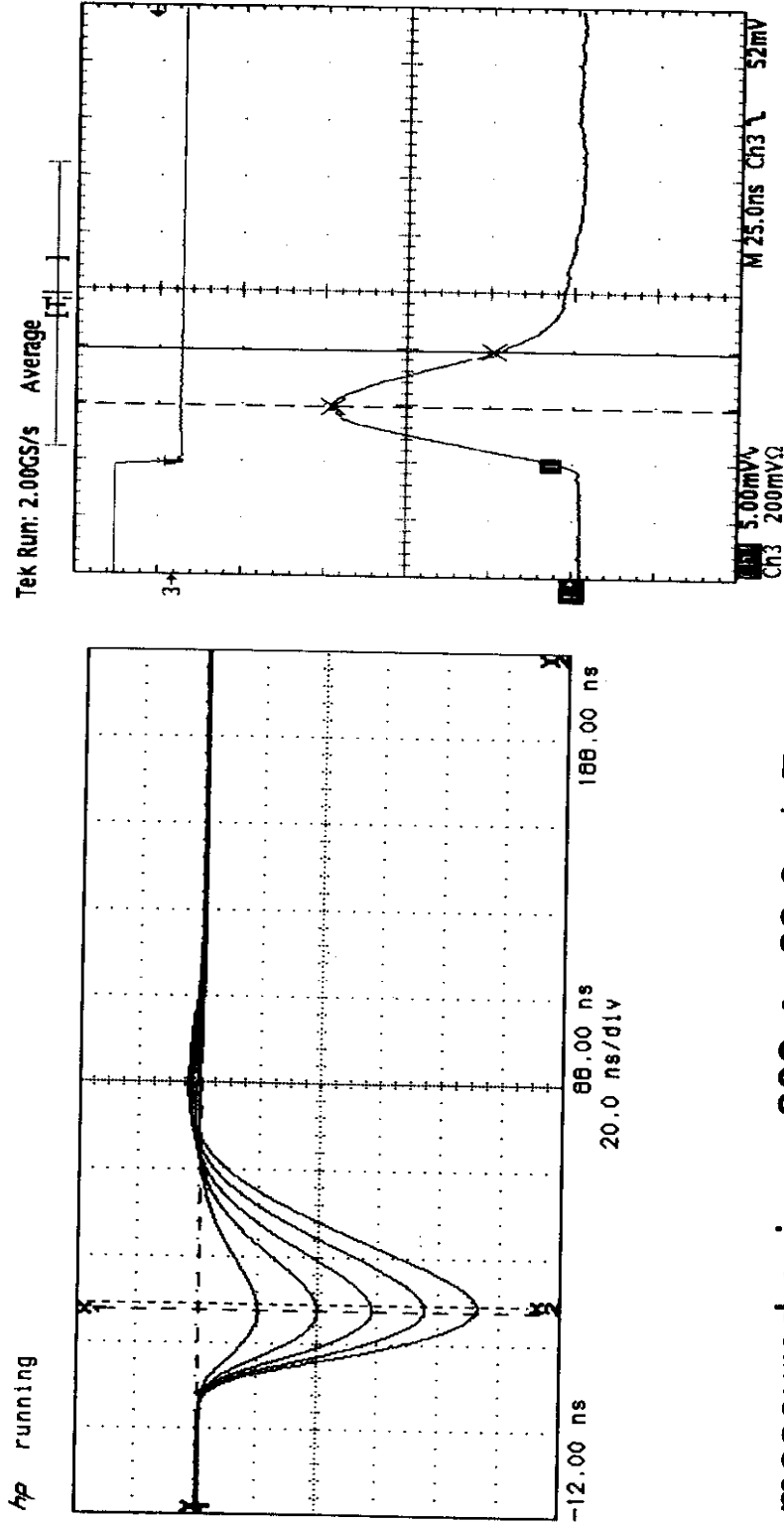
First prototyp readout chip

- Beetle 1.0

all submitted to CERN in april 2000

Beetle 1.0 Frontend Amplifier

Same like on BeetleFE testchip



measured noise = $303e^{-} + 33.6e^{-}/pF$

dynamic range: $\pm 10 \text{ MIP} = \pm 110.000e^{-}$

no peakshift for higher signals

power consumption: 1.88mW / channel

risetime = 25ns

gain = 14.5 mV / 11.000e⁻

remainder after 25ns = 30%

Pitch = 200 μm
 Thickness = 300 μm
 Length = 20 cm
 $\langle S \rangle = 32000 \text{ e-h pairs}$
 - 30% (Ballistic deficit)
 = 22400 e-h pairs
 divided by 2
 $\langle S \rangle = 11200 \text{ e-h pairs}$

C_coupling négligé car en série

Width W μm	X = W/P	C_coup	C_tot [pF/cm]	898	1795	24.95	6.24
10	0.05	500	0.89	955	1910	23.40	5.86
20	0.10	1000	0.97	1012	2024	22.11	5.24
30	0.15	1500	1.06	1069	2138	20.95	4.97
40	0.20	2000	1.14	1126	2252	19.89	4.73
50	0.25	2500	1.23	1183	2367	18.93	4.51
60	0.30	3000	1.31	1240	2481	18.05	4.32
70	0.35	3500	1.40	1298	2595	17.26	4.13
80	0.40	4000	1.48	1355	2709	16.54	3.97
90	0.45	4500	1.57	1412	2824	15.87	3.81
100	0.50	5000	1.65	1469	2938	15.26	3.67
110	0.55	5500	1.74	1526	3052	14.68	
120	0.60	6000	1.82				

ENC Beelle 50 - 33.6 C tot

ENC+ = 2.*ENC

S_m = Minimum gauche de la distribution de Landau

C_tot selon l'article de CMS, <100> et <111> avant irradiation

C_back Non utilisé

C_interstip = (0.9 + 1.7*X) Non utilisé

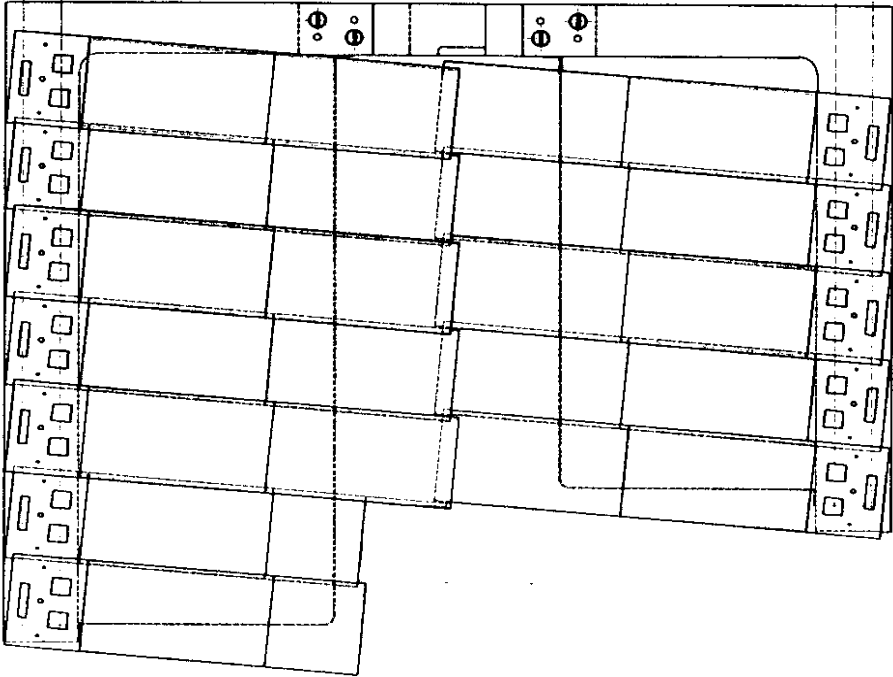
$C_{tot} = 0.8 + 1.7 X$

Ref: CMS Note 2009 / 011

\rightarrow no deterioration up to $\sim 24 \times 10^{14}$ equiv. $\Delta 17 \text{ eV N}$
 for <100> low-resistivity silicon

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SIL 17



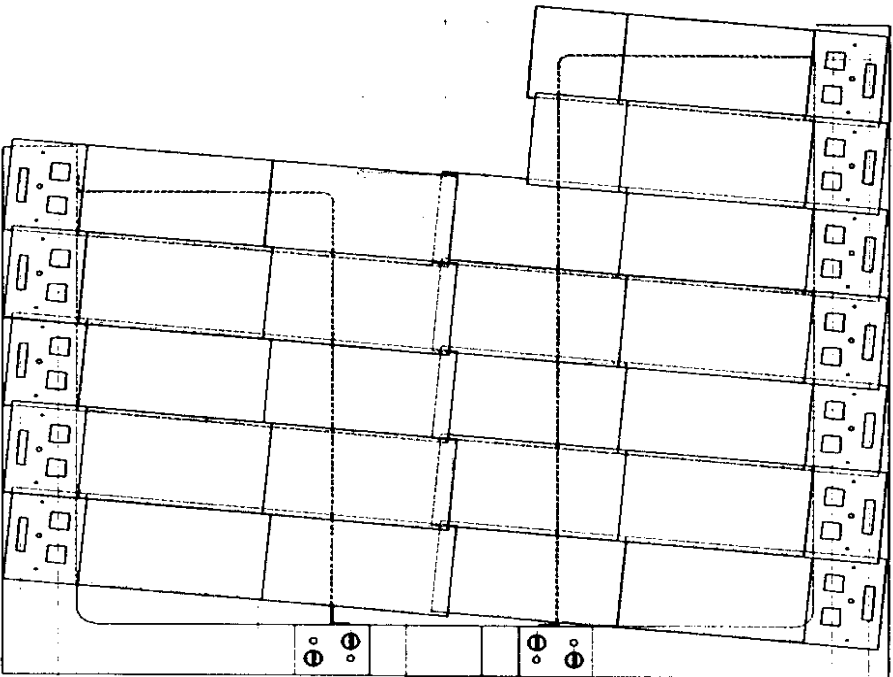
VER 1

B ↑

A ↑



VER 1



A ↑



VER 1

COOLING :

- REMOVE HEAT FROM R/O ELECTRONICS
- OPERATE DETECTORS AT -5 TO -10°C
(CMS/ATLAS)

APPROACH 1:

LIQUID COOLING CIRCUIT FOR R/O ELECTR.
+ "AIR" COOLING FOR DETECTORS

INTERESTING: "VORTEX" COOLING, TESTED
BY HERA-B FOR "STATION 8"

⇒ ALLOWS TO REACH $\sim -40^{\circ}\text{C}$

⇒ ENOUGH POWER FOR LARGE VOLUMES?

APPROACH 2:

LIQUID COOLING CIRCUIT FOR R/O ELECTR.
AND DETECTORS.

RELY ON THERMAL CONDUCTIVITY OF SUPPORT
STRUCTURE ⇒ USED IN CMS TRACKER

⇒ APPROPRIATE FOR "OPEN GEOMETRY"?

⇒ FOLLOW BOTH APPROACHES

DOUBLE-SIDED SILICON :

MANY DISADVANTAGES

- HANDLING

- COST

- PRODUCTION YIELD / QUALITY

CNN: "too complex"

HANAMITSU: "afraid cannot meet specifications"

- R/O OF STEREO VIEWS ?

- INFRASTRUCTURE, HOUSING OF R/O ELECTRONICS ?

ONE BIG ADVANTAGE

+ RADIATION LENGTH

(+ 300 μm \rightarrow 400 μm FOR BETTER SIGNAL/NOISE ?)

ON THE OTHER HAND:

* CURRENT PERFORMANCE STUDIES ASSURE

0.4% X° / COORDINATE MEASUREMENT

300 μm SILICON $\hat{=}$ 0.3% X°

* CURRENT SIMULATIONS SHOW

62% OF SECONDARIES FROM BEAM PIPE

27% OF SECONDARIES FROM TRACKING DET.

\Rightarrow VERY LITTLE ENTHUSIASM

\Rightarrow NEED STRONG ARGUMENTS FROM SIMULATION

\Rightarrow START WITH SINGLE-SIDED PROTOTYPES

Technical proposal of Si microstrip detector prototype for LHCb-ITR

1. Main parameters:

Technological Parameters	Value	Comments
Semiconductor type	N type Oxygenated Si ✓	Better rad hardness. Ref ROSE
Crystal	< 100 > ✓	Better rad hardness. Ref ROSE
Resistivity	Low: ~ 1kΩ · cm ✓	Better rad hardness. Ref ROSE
Wafer thickness	D ~ 300 μm ✓	Commercially available Oxygenation uniformity: OK
	D > 300 μm?? (2 ONLY IF DOUBLE-SIDED)	Oxygenation uniformity: possible Better S/N? Better efficiency?? Lower Cback?
Size (wafer diam)	4" 2 FOR PROTOTYPES	4" wafer oxygenation: done at IMB-CNM
	6" 2 FOR PRODUCTION	6" wafer oxygenation: not yet done
Implant type	P+ on n ✓	Ref CMS, ATLAS
	N+ on n	Old baseline
Breakdown protection	Guard ring structures Number of rings: 16?	Only on strip side
Individual strip biasing (AC readout)	Implanted resistors	Ref MPI
	Polisilicon resistors	More lithography steps
Backplane biasing	Edge contact	No backplane passivation removal Ref MPI: http://www.hll.mpg.de/atlas/bias/topBias.html
	Metal contact: N+ / Al / bonding	Open backplane passivation
Photolithography	Single sided 5 steps	1 passivation openings 2 p+ strip implant 3 resistors implant 4 metalization (Al) 5 contacts

D-SUBSTRATE

PRODUCERS :

* HANAATSU

- + RUN MASS PRODUCTION FOR ATLAS / CMS
- + KNOWN FOR RELIABLE QUALITY
- + ONLY MINOR MODIFICATIONS TO CMS DESIGN
- + WE PROVIDE SPECS, THEY TAKE CARE OF DETAILS
- + ATTRACTIVE PRICE : $< 10 \text{ CHF/cm}^2$ FOR CMS
- TURNAROUND / COST FOR PROTOTYPING ?

* "CNT" / BARCELONA

- + EXPERIENCE WITH DETECTORS FOR HIGH-RADIATION ENVIRONMENT (MEMBERS OF RD48/ROSE COLL.)
- + HAVE CAPACITY FOR MASS PRODUCTION
 - "is ready a big institute of micro-electronics, Oef"
- WE HAVE TO PROVIDE FULL SET OF MASKS
- QUALITY / YIELD IN MASS PRODUCTION ?

* "DETEKTOR" / KIEV

- + LONG-ESTABLISHED CONTACT TO V. PUGATCH
 - "their boss ^{was} is a PhD student of mine..."
- + HAVE CAPACITY FOR MASS PRODUCTION
- + WE PROVIDE SPECS, THEY TAKE CARE OF DETAILS
- + ATTRACTIVE PRICE FOR PROTOTYPE
- QUALITY / YIELD IN MASS PRODUCTION ?

⇒ KEEP OPTIONS OPEN, TRY TO GET PROTOTYPES FROM ALL THREE

SUMMARY

- DETECTOR SIMULATION / TRACKING STUDIES STARTED
 - * AIM:
 - ~ DETERMINE DETECTOR PARAMETERS
 - ~ CHECK INFLUENCE OF MATERIALS
 - * INTEGRATED INTO TRACKING GROUP
- 3 GEN OPTION
 - * DETECTOR OPTIMIZATION:
 - ~ GEN FOILS → LESS MATERIAL, SEGMENTATION
 - ~ READOUT PCB → CAPACITANCE
 - ~ GAS MIXTURES → DIFFUSION, CLUSTER SIZE, SPARKING
 - * STUDY OF SPARKING PROPERTIES & DAMAGE
- SILICON OPTION
 - * WORK HAS STARTED:
 - ~ STATION LAYOUT
 - ~ COOLING
 - ~ SPECS FOR PROTOTYPE DETECTORS
 - ~ CONTACTS TO MANUFACTURERS (→ HANAFATSU!)
- ... ALSO STARTING TO WORRY ABOUT SUPPORTS / FRAMES..